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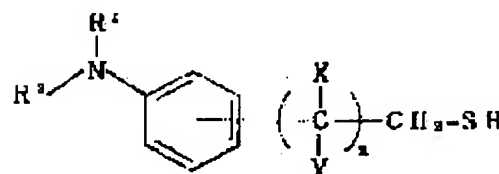
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(54) ION EXCHANGE RESIN AND MANUFACTURE OF BISPHENOL USING THIS RESIN

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain modified strongly acidic sulfonic acid-type ion exchange resin which shows high acetone conversion rate and good selectivity by ionic- bonding anilines having a mercapto group shown by the formula to a part of a sulfonic group of strongly acidic sulfonic acid-type ion exchange resin.

SOLUTION: The modified strongly acidic sulfonic acid-type ion exchange resin is available as a catalyst in the case of producing bisphenol A by bonding reaction of bisphenol e.g. phenol and acetone and is manufactured by ionic- bonding anilines having a mercapto group shown by the formula to strongly acidic sulfonic acid-type ion exchange resin. In the formula, R1 and R2 denote hydrogen atom, 1-4 C alkyl group or aryl group; X and Y denote hydrogen atom, 1-6 C alkyl group, 5-10 C cycloalkyl group or aryl group; (n) denotes integer of 1-3; and when (n) is 2 or 3, each of a plurality of X and Y may denote another group.



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